

| Ref # | Hits   | Search Query             | DBs   | Default Operator | Plurals | Time Stamp       |
|-------|--------|--------------------------|---|------------------|---------|------------------|
| S1    | 3091   | photo near pattern       | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:36 |
| S2    | 24887  | photoresist near pattern | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:36 |
| S3    | 27744  | S1 or S2                 | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:37 |
| S6    | 15166  | i-line or KrF            | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:37 |
| S7    | 1807   | S3 and S4                | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:38 |
| S8    | 10744  | ArF or UvU or EUF        | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:38 |
| S9    | 128    | S7 and S8                | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:38 |
| S10   | 411399 | resist                   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:38 |
| S11   | 66     | S9 and S10               | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:51 |
| S12   | 2      | "4491628".pn.            | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2005/08/25 07:56 |

|     |        |                                |   |    |    |                  |
|-----|--------|--------------------------------|---|----|----|------------------|
| S13 | 1      | 10/719083                      | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/08/25 07:56 |
| S14 | 336    | ("4491628").URPN.              | USPAT   | OR | ON | 2005/08/25 08:43 |
| S15 | 965    | tri-level                      | USPAT   | OR | ON | 2005/08/25 08:43 |
| S16 | 68113  | photoresist                    | USPAT   | OR | ON | 2005/08/25 08:43 |
| S17 | 21     | S15 near S16                   | USPAT   | OR | ON | 2005/08/25 10:05 |
| S18 | 454581 | polymer                        | USPAT   | OR | ON | 2005/08/25 10:05 |
| S19 | 365962 | silicon                        | USPAT   | OR | ON | 2005/08/25 10:06 |
| S20 | 191357 | mask                           | USPAT   | OR | ON | 2005/08/25 10:06 |
| S21 | 1      | S18 near S19 near S20          | USPAT   | OR | ON | 2005/08/25 10:09 |
| S22 | 1      | silicon near polymer near mask | USPAT   | OR | ON | 2005/08/25 10:09 |
| S23 | 1      | silicon near polymer near etch | USPAT   | OR | ON | 2005/08/25 10:09 |
| S24 | 357    | S18 near S20                   | USPAT   | OR | ON | 2005/08/25 10:14 |
| S25 | 3334   | i-line                         | USPAT   | OR | ON | 2005/08/25 10:14 |
| S26 | 191357 | mask                           | USPAT   | OR | ON | 2005/08/25 10:14 |
| S27 | 2761   | S25 and S26                    | USPAT   | OR | ON | 2005/08/25 10:15 |
| S28 | 365962 | silicon                        | USPAT   | OR | ON | 2005/08/25 10:15 |
| S29 | 2131   | S27 and S28                    | USPAT   | OR | ON | 2005/08/25 10:15 |
| S30 | 186985 | poly                           | USPAT   | OR | ON | 2005/08/25 10:15 |
| S31 | 692    | S29 and S30                    | USPAT   | OR | ON | 2005/08/25 10:53 |
| S32 | 1874   | gas near absorbing             | USPAT   | OR | ON | 2005/08/25 10:54 |
| S33 | 766    | oxygen near absorbing          | USPAT   | OR | ON | 2005/08/25 10:54 |
| S34 | 200051 | resist                         | USPAT   | OR | ON | 2005/08/25 10:54 |
| S35 | 96988  | spin                           | USPAT   | OR | ON | 2005/08/25 10:54 |
| S36 | 14776  | bake                           | USPAT   | OR | ON | 2005/08/25 10:54 |
| S39 | 151804 | water adj soluble              | USPAT   | OR | ON | 2005/08/25 10:56 |
| S40 | 454581 | polymer                        | USPAT   | OR | ON | 2005/08/25 10:56 |
| S41 | 20443  | S39 near S40                   | USPAT   | OR | ON | 2005/08/25 10:56 |
| S42 | 3403   | S35 and S36                    | USPAT   | OR | ON | 2005/08/25 10:56 |
| S43 | 36     | S41 and S42                    | USPAT   | OR | ON | 2005/08/25 10:57 |
| S44 | 30     | S43 and S34                    | USPAT   | OR | ON | 2005/08/25 11:04 |
| S46 | 2594   | S32 or S33                     | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/08/25 10:57 |
| S50 | 195    | S34 and S46                    | USPAT   | OR | ON | 2005/08/25 11:05 |
| S51 | 23     | S50 and S39                    | USPAT   | OR | ON | 2005/08/25 11:14 |

|     |       |  |   |    |    |                  |
|-----|-------|--|---|----|----|------------------|
| S52 | 53    | organic adj polysilane                 | USPAT   | OR | ON | 2005/08/25 11:14 |
| S53 | 68113 | photoresist                            | USPAT   | OR | ON | 2005/08/25 11:14 |
| S54 | 8     | S52 and S53                            | USPAT   | OR | ON | 2005/08/25 14:15 |
| S55 | 0     | organic adj polysilane adj photoresist | USPAT   | OR | ON | 2005/08/25 13:46 |
| S56 | 0     | organic adj polysilane adj resist      | USPAT   | OR | ON | 2005/08/25 13:46 |
| S57 | 0     | organic adj polysilane near resist     | USPAT   | OR | ON | 2005/08/25 13:46 |
| S58 | 13    | organic adj polysilane and resist      | USPAT   | OR | ON | 2005/08/25 13:46 |
| S61 | 1     | 10/712,446                             | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2005/08/25 14:16 |